



2826

PATENT
Customer No. 22,852
Attorney Docket No. 04329.2306

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Yoshio Ozawa et al.

Serial No.: 09/559,757

Filed: April 27, 2000

For: SEMICONDUCTOR DEVICE AND
METHOD OF MANUFACTURE
THEREOF

Group Art Unit: 2826

Examiner: Johannes P. Mondt

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Assistant Commissioner for Patents
Washington, DC 20231

Sir:

AMENDMENT

In reply to the Office Action dated October 10, 2001, the period for response extending through January 10, 2002, please amend the application as follows:

IN THE CLAIMS:

Please cancel claim 6 without prejudice or disclaimer of the subject matter therein, and amend claims 1 – 5 and 7 as follows:

1. (Amended) A semiconductor device comprising:

a semiconductor substrate having a main plane in which a channel of a transistor is formed, the semiconductor substrate comprising a first region and a second region defined in a section taken along a direction of a channel length, the second region having a surface located lower than that of the first region, and the second region being connected to the first region;

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